

Amendments to the Claims:

The listing of claims will replace all prior versions, and listings of claims in the application:

Listing of Claims:

Claims 1 – 10 (cancelled)

Claim 11 (currently amended) A non-volatile memory structure, including:
 a base;
 a gate dielectric layer on the base, wherein the gate dielectric layer has ~~with an~~ increased electron trapping density and has at least one kind of hetero element, other than Nitrogen;
 a gate electrode layer on the top of the said gate dielectric layer; and
 a source/drain electrodes at the base on both sides of the said gate dielectric layer.

Claim 12 (previously presented) The non-volatile memory structure as claimed in claim 11, where the gate dielectric layer in turns from bottom to the top including a first oxide layer, a nitride layer and a second oxide layer.

Claim 13 (previously presented) The non-volatile memory structure as claimed in claim 11, where the hetero elements used are any one within Germanium (Ge), Silicon (Si), Oxygen (O₂), Oxygen (O) separately or multiple mixture therefrom.

Claim 14 (previously presented) The non-volatile memory structure as claimed in claim 11, where the hetero elements used are compounds of Germanium (Ge), Silicon (Si), Oxygen (O).

Claim 15 (previously presented) The non-volatile memory structure as claimed in claim 11, where the hetero elements used are compounds of Germanium (Ge).

Claim 16 (previously presented) The non-volatile memory structure as claimed in claim 11, where the hetero elements used are compounds of Oxygen (O).